

Abstract of the Disclosure

A substrate processing apparatus for feeding a processing liquid and processing a substrate with the processing liquid. The apparatus includes a holding member for holding the substrate, and a lower side member which is moved relatively with respect to the back surface of the substrate held by the holding member between a processing position near the substrate undersurface and a retreat position remote from the substrate undersurface. The processing liquid is fed into a gap between the lower side member moved to the processing position and the back surface of the substrate held by the holding member, and the substrate undersurface is processed.